

**Supplemental Materials for**  
**Revealing pressure-induced softening/weakening mechanism in**  
**representative covalent materials**

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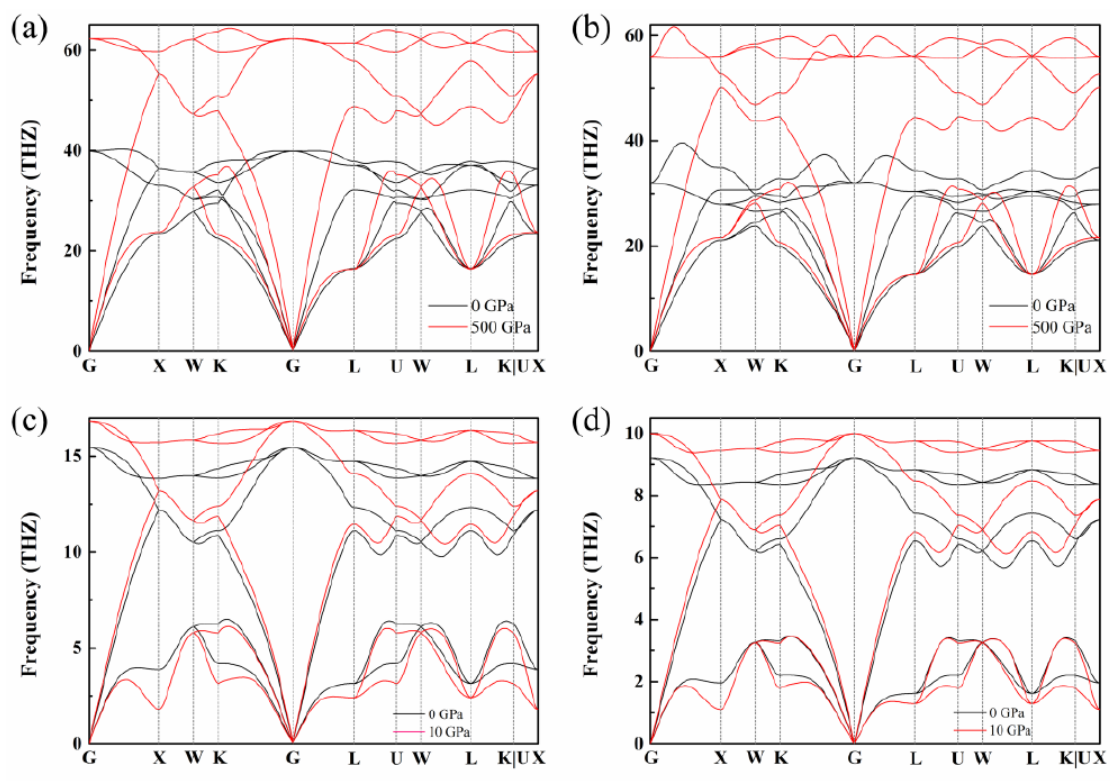
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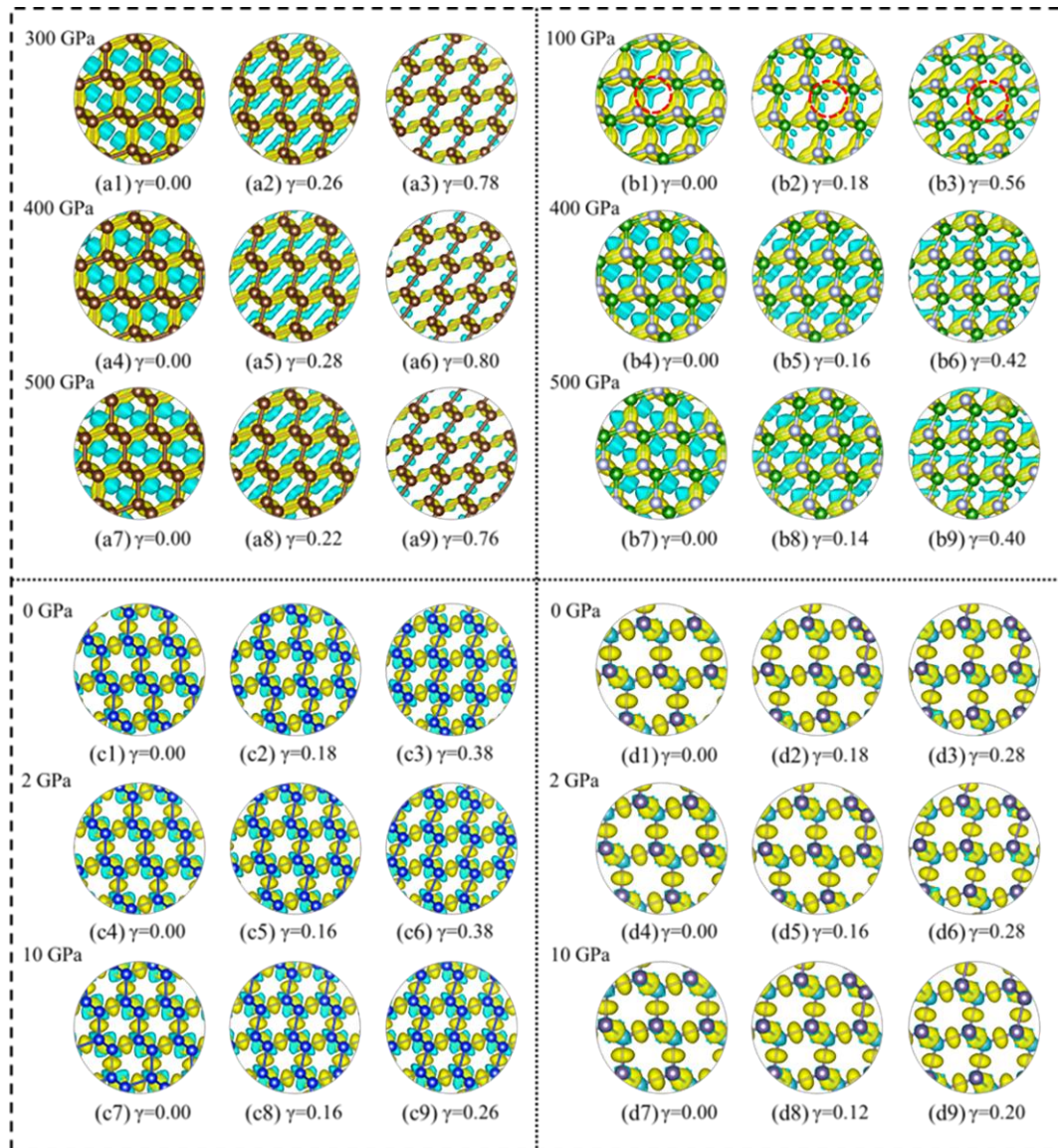
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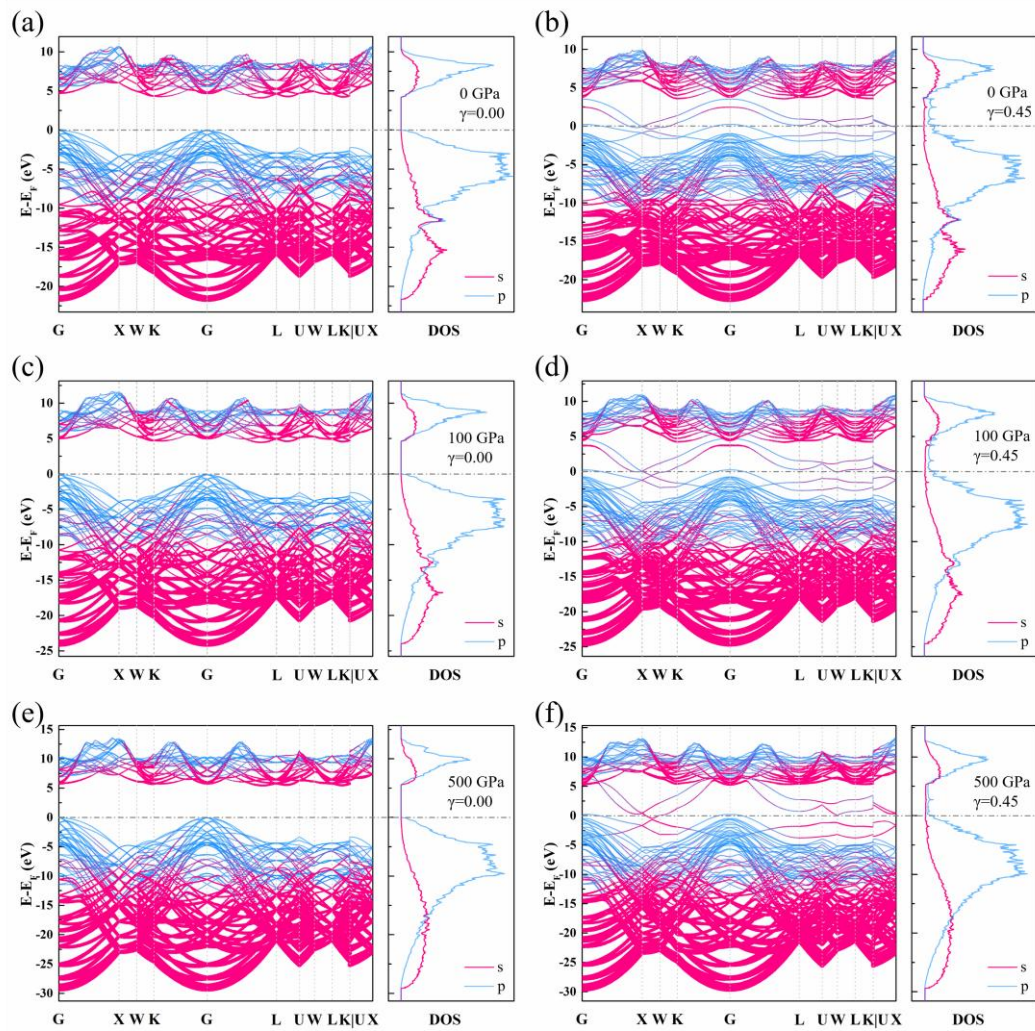
**Fig. S1.** Calculated phonon dispersion curves of (a) diamond, (b) c-BN, (c) Si and (d) Ge under zero and high pressures.



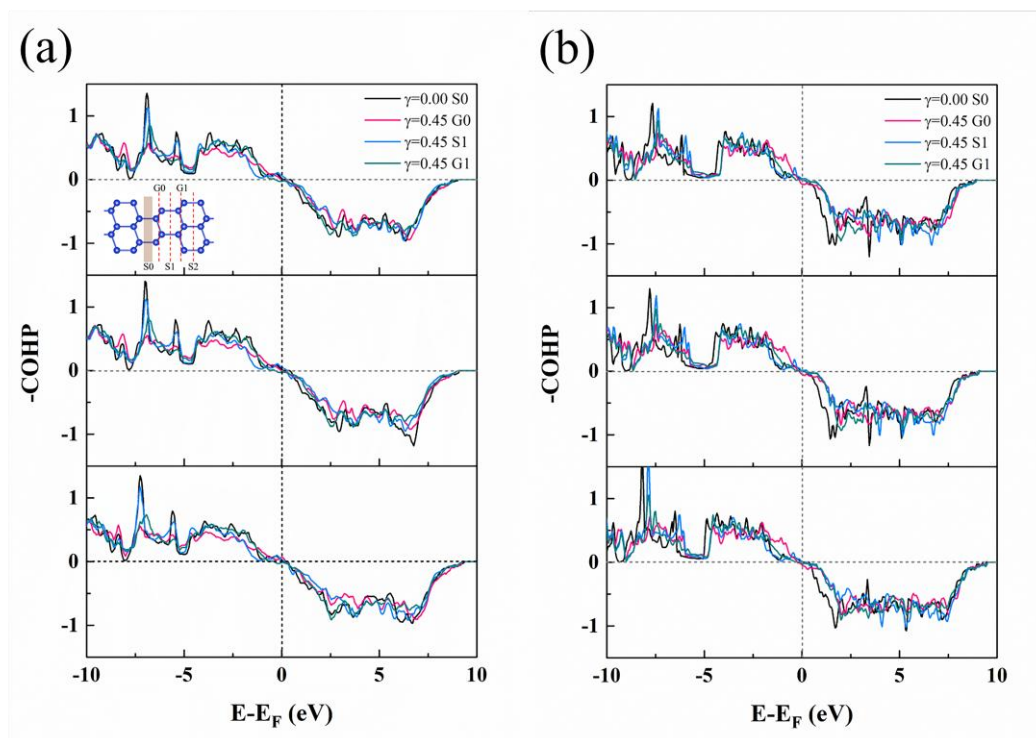
**Fig. S2.** Calculated isosurfaces of the VCDD of (a1)-(a9) diamond, (b1)-(b9) c-BN, (c1)-(c9) Si and (d1)-(d9) Ge under different strains along the  $(111)[11\bar{2}]$  shearing path under different pressures. The unit of VCDD is electrons/Bohr<sup>3</sup>, and a same isosurface level of  $\pm 0.0305$ ,  $\pm 0.0340$ ,  $\pm 0.0375$  electrons/Bohr<sup>3</sup> is used for diamond under 300, 400 and 500 GPa,  $\pm 0.022$ ,  $\pm 0.033$ ,  $\pm 0.036$  for c-BN under 100, 400 and 500 GPa,  $\pm 0.008$  for Si and  $\pm 0.005$  for Ge under 0, 2, 10 GPa, respectively. Blue and yellow regions signify the states of charge depletion (negative) and accumulation (position), respectively.



**Fig. S3.** Fat band structures and the corresponding DOS curves of diamond slipping with various displacements ( $\gamma=0.00, 0.45$ ) along the shuffle-set plane at different pressures.



**Fig. S4.** The COHP curves of the bonds around the slip plane “S0” in (a) Si and (b) Ge under various displacements ( $u=0.00$  and  $u=0.45$ ) at different pressures.





**Table S1.** The calculated lattice constant  $a$  (in Å), polycrystalline shear ( $G_{\text{VRH}}$ ) and bulk ( $K_{\text{VRH}}$ ) moduli (in GPa), Pugh ratio ( $G_{\text{VRH}}/B_{\text{VRH}}$ ), ideal strength  $\sigma_{\text{min}}$  and  $\tau_{\text{min}}$  (in GPa) under uniform strain along the weakest  $[111]$  tensile and  $(111)[11\bar{2}]$  shear direction, respectively, the unstable GSFES  $\gamma_{\text{US}}$  (in  $\text{J}/\text{m}^2$ ) and Peierls stresses  $\tau_{\text{P}}$  (in GPa) along the  $[1\bar{1}0]$  and  $[11\bar{2}]$  directions on the shuffle-set and glide-set plane for diamond, c-BN and Si, together with the experimental data and other theoretical values for comparison.

Material	$a$	$G_{\text{VRH}}$	$B_{\text{VRH}}$	Pugh ratio	$\sigma_{\text{min}}$	$\tau_{\text{min}}$	$\gamma_{\text{US-shuffle-[110]}}$	$\gamma_{\text{US-glide-[112]}}$	$\tau_{\text{P-shuffle-[110]}}$	$\tau_{\text{P-glide-[112]}}$
Diamond	3.535	541.34	467.85	1.157	92.33	93.2	9.97	5.77	14.3	14.8
	3.534	543.8	471.18	1.154	95 [2]	93 [2]	9.93 [1]	5.77 [3]	13.3 [3]	19.5 [3]
	[1]	[1]	[1]	[1]						
	3.567	545 [6]	468 [6]	1.165	90.7	93.9	9.72 [3]	5.74 [7]	13.0 [8]	
	[4,5]		[6]	[1]	[1,3]					
c-BN	3.583	402.73	403.22	0.999	65.4	65.3	7.47	3.76	10.83	2.83
	3.583	403.51	404.41	0.998	64.9	65.2 [3]	7.44 [3]	3.79 [3]	12.4 [3]	3.79 [3]
	[1]	[1]	[1]	[1]	[3]					
	3.62		400		65.9	64.9 [1]	7.20 [8]	3.43 [8]	10.3 [8]	3.73 [8]
	[9]		[10]		[1]					
Si	5.403	63.24	96.83	0.6531	20.97	7.25	1.45	1.82	1.3	14.28
	5.39	56.6	97.9		19.2	7.8 [8]	1.67 [14]	1.91 [14]	1.7 [8]	10-26[15]
	[11]	[12]	[13]		[8]					
	5.375	57.9	99.2		22 [2]	6.8 [2]		1.89 [16]	0.6-2.8	
	[12]	[11]	[8]					[15]		
Ge	5.65	47.12	72.35	0.6513	14.38	5.08	1.10	1.55	0.60	13.78
	5.65	46 [17]	83 [17]	0.5542	14 [2]	4.3 [2]	1.20 [18]		0.4-0.5	
	[17]			[17]					[18]	
	5.66	47 [19]	77 [19]	0.6104		5.4 [17]				
	[19]		[19]							

## Reference

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